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LaMeS – Layered structures of Metal Sulphides

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Aim and Purpose

- Sputtering of high quality novel 2D sulphide films.
- Primarily WS_2 , MoS_2 , SnS_2 and combinations thereof.
- Study the influence of the energetic particle bombardment onto the proposed 2D-materials.
- Characterize and evaluate the sputtered 2D-materials films from a fundamental standpoint.



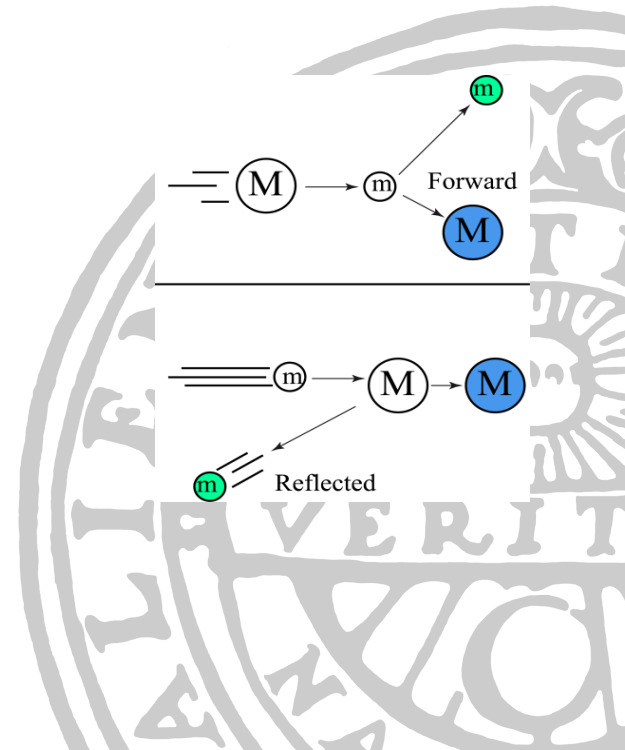
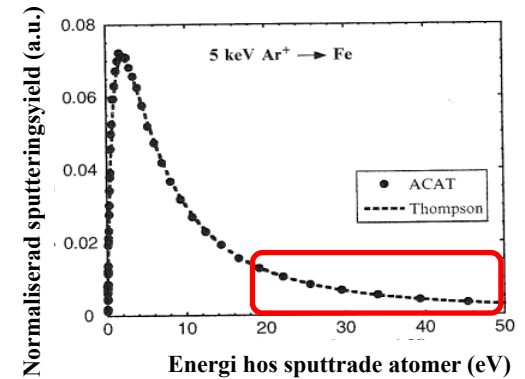


Energetic Particles during Sputter Deposition

Sputtered atoms of high energy

Reflected Ar from the target

Negative ions from the target





Sputtering onto Sensitive Substrates – Graphene, MoS₂ and WS₂

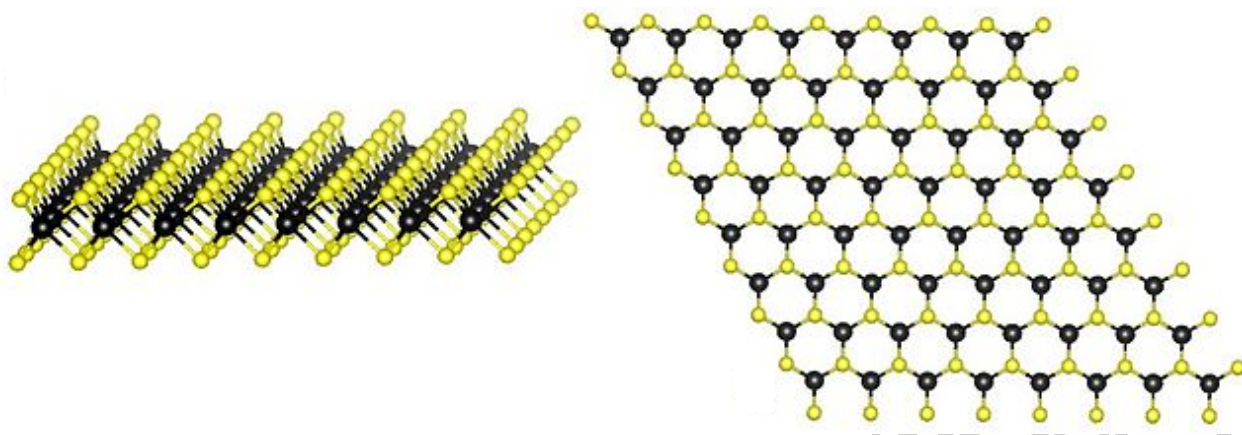
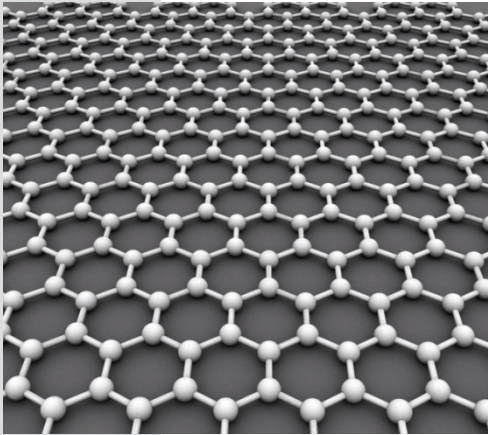
The energy threshold for defect formation:

Graphene defects: P. Ahlberg, et al., APL Materials 4, 046104 (2016)

WS₂ on Graphene: F. O. L. Johansson, et al., Appl. Phys. Lett. 110, 091601 (2017)

~33 eV for Ar onto graphene¹

~ 8 eV for MoS₂² ~ 7 eV for WS₂³



A hexagonal WS₂ or MoS₂ monolayer,
W or Mo (black) and S (yellow) (left).
A WS₂ or MoS₂ monolayer from above (right).

¹ Chen et al. APL 103 (2013) ² Muratore et al. APL 104 (2014) ³ Wang et al Phys.Chem.Chem.Phys.(2015)



- Where are Sn and W in the structure?
- Combine other 2D-materials; $WS_2 + MoS_2$, $SnS_2 + MoS_2$, $WS_2 + MoS_2 + SnS_2$
- What is the thinnest possible fully covering film?
- What is the thickest film still having epitaxial structure ?
- What is the processing window with respect to temperature and processing pressure ?

